Virtual Project on the History of ALD: overview and current status

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Atomic Layer Deposition (ALD), based on the repeated, self-terminating gas—solid reactions of at least two gaseous compounds on a solid substrate, has become a disruptive key enabling materials manufacturing method. By its inventors, this method was given the name Molecular Layering (1960s, Soviet Union) and Atomic Layer Epitaxy (1970s, Finland). While the original names still live on, gradually since the 1990s, "ALD" has evolved to be the mostly commonly used name for the technique.

<u>Virtual Project on the History of ALD (VPHA)</u> was set up in summer 2013 as an open effort, in which volunteered scientists from all around the world work together in an atmosphere of openness, respect and trust to better understand the early days of ALD. VPHA has already resulted in joint publications, a tutorial, two essays, an exhibition, <u>Wikipedia</u> updates, and a blog; see http://vph-ald.com and VPHA publication plan for details.

As of April 2016, VPHA takes a next leap. The plan is to complete the central work during summer 2016, namely the listing, reading and commenting on early ALD works (there are over 300 ALD publications to read up to year 1986); and create a joint poster to ALD 2016 in Dublin. A review is also being planned, with summaries of theses, conferences, and reviews.

With this abstract at the <u>HERALD Working group 2</u> workshop and <u>4th annual seminar</u> of <u>ALDCoE</u> "ALD precursors and processes", we invite more voluntary contributors to join the VPHA. People from all backgrounds and skills are warmly welcome to contribute.

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